Amendments to the Specification

Please amend the paragraph on page 7, at lines 1-8, for the second time (first amendment made August 30, 2002), as follows:

The electron beam irradiation means includes an electron gun and the collimator means includes a condenser lens for collimating the electron beam emitted from the electron gun to a parallel beam and an aperture plate having an aperture inserted between the condenser lens and the semiconductor device, for limiting a spot size of electron beam such that the electron beam impinges an opening portion. The electron beam irradiation means preferably includes means for moving the sample under test with respect to the electron beam in order to scan the ~~ample~~ sample with electron beam.

Please amend the paragraph on page 7, at lines 9-16, as follows:

Alternatively, the electron beam irradiation means includes an electron gun and the collimator means may include a first condenser lens for collimating the electron beam emitted from the electron gun to parallel beam, a second condenser lens arranged such that it constitutes an afocal system, an objective lens and an aperture plate having an aperture inserted ~~into~~ between the first condenser lens and the second condenser lens for limiting a spot size of the electron beam. It may further include means for moving the sample under test with respect to the electron beam in order to scan the ~~ample~~ sample with electron beam.

Please amend the paragraph on page 9, at lines 20-27, as follows:

The data processing means may includes means for storing a current value corresponding to an electron beam irradiated portion, which is obtained in a location of the sample having no dust (particle or residue), means for comparing the current value stored in the storing means with a current value corresponding to an electron beam irradiated position in the same pattern portion of an unknown sample as that of

the sample and means for determining the existence and size of dust from a difference between a rising and falling positions of the current obtained by the comparison.

Please amend the paragraph on page 27, at lines 7-13, as follows:

Since the electron beam has a finite cross sectional area, the compensation current starts to rise at a time when the electron beam crosses an edge portion of the bottom of the contact-hole, as shown in FIG. 6(b). When the electron beam ~~exists~~ exits from the bottom portion of the contact-hole, compensation current starts to decrease from the saturated value and becomes zero when the electron beam completely leaves the contact hole.

Please amend the paragraph on page 39, at lines 4-8, as follows:

Since the contact-hole has a three-dimensional structure, it is very preferable to obtain a test result which can clearly show a feature of the ~~tree-dimensional~~ three-dimensional contact-hole. Although a method for obtaining an exact three-dimensional structure of the contact-hole will be described in detail later, the method will be described briefly here.

Please amend the paragraph on page 59, at lines 25-28, as follows:

This test can be done according to the test flowchart shown in FIG. 26 by using the ~~dvice~~ device shown in FIG. 25 as in the case shown in FIG's. 29(a) and 29(b) and FIG's. 30(a) and 30(b). In this test, however, the electron gun 112 generates the line-shaped electron beam.